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(54) Title: AREA SELECTIVE DEPOSITION OF METAL CONTAINING FILMS

(57) Abstract: Processes of selectively depositing a metal-containing film comprise: providing a surface having a plurality of materials exposed thereon simultaneously, and exposing the surface to a vapor of a metal-containing film-forming composition that contains a precursor having the formula: $L_xM(-N(R)-(CR'_2)_n-NR''_2)$ wherein M is a Group 12, Group 13, Group 14, Group 15, Group IV or Group V element; x+1 is the oxidation state of the M; L is an anionic ligand, independently selected from dialkylamine, alkoxy, alkylimine, bis(trialkylsilylamine), amidinate, betadiketonate, ketoimine, halide, or the like; R, R' each are independently a C₁-C₁₀ linear, branched or cyclic alkyl, alkenyl, or trialkylsilyl group; R' is H or a C₁-C₁₀ linear, branched or cyclic alkyl, alkenyl or trialkylsilyl group; n = 1 - 4, wherein at least one of the materials is at least partially blocked by a blocking agent from the deposition of the metal-containing film through a vapor deposition process.